



IFW

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Koichi KANAYA et al.

Group Art Unit: 1762

Application No.: 10/565,653

Examiner: K. CHEN

Filed: January 24, 2006

Docket No.: 126247

For: VAPOR DEPOSITION APPARATUS AND VAPOR DEPOSITION METHOD

SUMMARY OF SUBSTANCE OF PERSONAL INTERVIEW

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

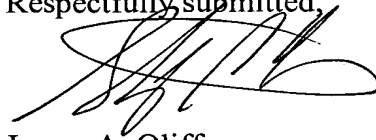
Applicants appreciate the courtesies shown to Applicants' representative by Examiners Chen and Cleveland in the January 7, 2009 personal interview. Applicants' separate record of the substance of the interview is incorporated into the following remarks.

The claim amendments and arguments set forth in Applicants' December 18, 2008 Amendment were discussed. In particular, the new claims 20-21 were discussed and explained. In particular, it was pointed that the claims now recite steps of "selecting" a particular susceptor having a maximum pocket depth and having a warped inverted U shape, and "maintaining" the maximum depth of less than 0.4 mm during vapor growth deposition to avoid slip dislocations.

The Examiners agreed that the next Office Action would not be a final rejection.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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Registration No. 36,101

JAO:SPC/add

Date: January 8, 2009

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